



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Kouji TOMETSUKA

Serial No.: 09/911,741

Filed: July 25, 2001

For: SUBSTRATE PROCESSING APPARATUS AND METHOD

Group Art Unit: 1763

Examiner: R.N. Kackar

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4/18/03
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AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

This is in response to the Official Action of November 15, 2002, in connection with the above-identified application. The period for response has been extended to expire on April 15, 2003, by the filing herewith of a Petition for a Two Month Extension of Time and payment of the required fee.

Please amend the above-identified application as follows.

IN THE CLAIMS:

Please replace claims 1-3 and 6-8 with the following amended claims.

1(Amended). A substrate processing apparatus, comprising:
a stocker which stores a multiplicity of dummy substrates;
a reaction chamber which cleans one or more dummy substrates selected among the dummy substrates stored in the stocker and batch-processes a plurality of process substrates to be used for producing semiconductor products;
a boat which loads into the reaction chamber the process substrates and a portion of the dummy substrates stored in the stocker in order to process the process substrates and loads said one or more dummy substrates to clean same;

GROUP 1700
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